

## INFORMATION DISCLOSURE CITATION

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Applicant	Ogasawara et al.		
Filing Date	June 25, 2003	Prior Group:	2877

U.S. PATENT DOCUMENTS						
Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate
HP	5,315,123	5/1994	Itoh et al.	_____	_____	
HP	5,285,075	2/1994	Minamide et al.	_____	_____	
HP	5,136,169	8/4/92	Smith et al.	_____	_____	
HP	4,808,829	2/1989	Okumura et al.	_____	_____	
HP	4,650,983	3/1987	Suwa	_____	_____	
HP	4,636,968	1/1987	Gotou et al.	_____	_____	
HP	4,443,703	4/1984	Shimazu et al.	_____	_____	
HP	4,376,249	3/1983	Pfeiffer et al.	_____	_____	
HP	4,199,688	4/1980	Ozasa	_____	_____	

FOREIGN PATENT DOCUMENTS						
Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No	
		None				

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)	
HP	Goodberlet et al., "Spatial-Phase-Locked Electron-Beam Lithography with a Delay-Locked Loop," J. Vac. Sci. Technol. (1997), B15(6): 2293-97
HP	Smith et al., "A New Approach to High Fidelity E-Beam and Ion-Beam Lithography Based on an <i>in situ</i> Global-Fiducial Grid," J. Vac. Sci. Technol. (1991), B9(6):2992-95
HP	Smith et al., "Application of Moiré Techniques in Scanning-Electron-Beam Lithography and Microscopy," J. Vac. Sci. Technol. (1975), 12: 1262-65

Examiner	<i>HP</i>	Date Considered	11/8/04
*Examiner:	Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.		
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